

B. Remarks

The claims are 1-14, with claims 1 and 4 being independent.

Reconsideration of the present claims is respectfully requested.

Claims 1-6 stand rejected under 35 U.S.C. §102(b) as being anticipated by Ohkuma (EP 0 734 866). Applicants respectfully traverse this rejection.

Ohkuma simply fails to teach or suggest several key features of the presently claimed invention. Ohkuma is silent with regard to forming a second photosensitive material layer on a first photosensitive material layer. Instead, Ohkuma teaches the formation of a coating resin layer on its photosensitive material layer. While Ohkuma indicates that polymethyl isopropenyl ketone may be used as the material of its photosensitive material layer, the material used for the coating resin layer is typically a hardening resin having a negative photosensitive property. See, inter alia, Ohkuma [0053], [0077].

It is, then, clear that Ohkuma does not anticipate the present invention. According to the present invention, a second positive photosensitive material layer is formed on a first positive photosensitive material layer; in Ohkuma, there is no such second layer on the first. According to the present invention, the second positive photosensitive material layer contains mainly polymethyl isopropenyl ketone; in Ohkuma, the first photosensitive material layer may contain polymethyl isopropenyl ketone. Hence, Ohkuma does not disclose (or suggest) each and every claim limitation. Accordingly, Applicants respectfully request withdrawal of the §102(b) rejections of claims 1-6.

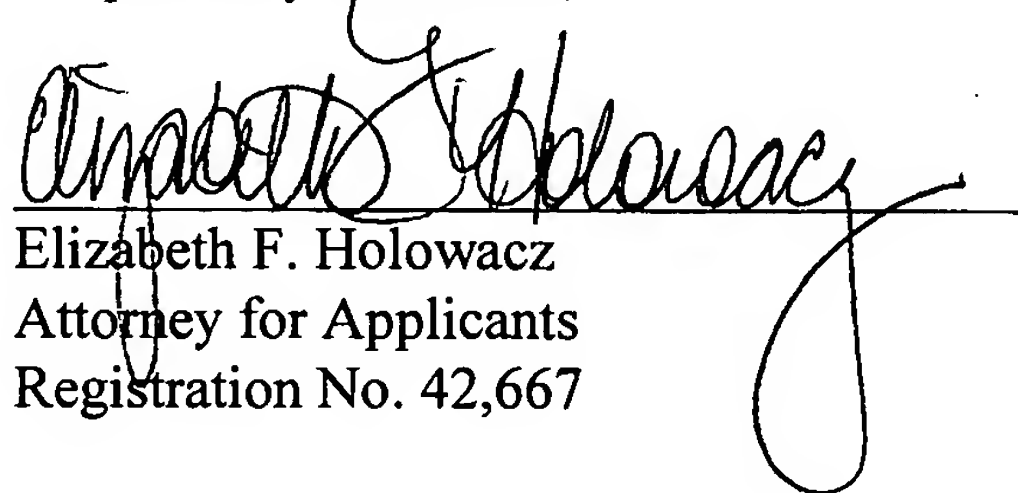
Claims 1-14 stand rejected under 35 U.S.C. §102(e) as being anticipated by Miyagawa (U.S. Patent Application Publication No. 2003/0011655). Applicants

respectfully traverse this rejection. In fact, Applicants submit that Miyagawa is not even prior art to the present invention. The present invention is entitled at least to an invention date of July 10, 2002, the date on which the priority application for the present case was filed. Hence, Miyagawa, filed on July 10, 2002, was not filed before the present invention was invented by the Applicants. Applicants' attorney shall forward the translation of the priority application upon receipt of it from Applicants. Accordingly, Applicants respectfully request withdrawal of the §102(e) rejection based upon Miyagawa.

In view of the foregoing remarks, favorable reconsideration and passage to issue of the present case is respectfully requested. Should the Examiner believe that issues remain outstanding, the Examiner is respectfully requested to contact Applicants' undersigned attorney in an effort to resolve such issues and advance the case to issue.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our below listed address.

Respectfully submitted,



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